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PATENT NUMBER and  
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10038084	01/03/2002	267	295	2814	A.D. MAI

\*\*APPLICANTS: Falster Robert;

\*\*CONTINUING DATA VERIFIED:

THIS APPLICATION IS A DIV OF 09/737,715 12/15/2000 PAT 6,342,725  
WHICH IS A CON OF 09/387,288 08/31/1999 PAT 6,236,104  
WHICH CLAIMS BENEFIT OF 60/098,902 09/02/1998

\*\* FOREIGN APPLICATIONS VERIFIED:

PG-PUB <input type="checkbox"/> DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO MEMC 98-3052 (2512.2)
35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no	
Verified and Acknowledged Examiners's initials	
TITLE : Silicon on insulator structure having a low defect density device layer and a process for the preparation thereof	

U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L (Rev. 12-94)

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
Assistant Examiner		Total Claims	Print Claims for O.G.
		DRAWING	
Primary Examiner		Sheets Drwg.	Figs. Drwg.
PREPARED FOR ISSUE		Applicati n Examiner	
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